Runsheet Heater Arrays

Nr. Process step	Substep	Parameter	Comments
1 - Substrate clean	Acetone rinse		
	IPA rinse		
	Oxygen plasma	Time: 2 min Power: 100 W Pressure: 270 mTorr	
	Dehydration bake	Time: 10 min Temperature: 180 degC	
2 – HMDS	Run saved HMDS recipe in oven		
3 – Lithography	Spincoating AZ 9260	Time: 45 sec Speed: 1500 rpm Acc: 100 rpm/s	Recipe "AZ_9260_1500_ML"
	Soft bake	Time: 5 min Temperature: 110 degC	
	Exposure	Time: 3 x 14.5 sec Rest: 5 sec Hard contact Gap: 70 µm	Suss aligner Lamp @ 350 W
	Developing	AZ 400k : DI → 1:3.5 Time: ca. 6 min	Time varies / microscope check
4 – Pre-sputter clean	Oxygen plasma descum	Time: 50 sec Power: 100 W Pressure: 270 mTorr	
5 – Sputtering	Denton: Si	Pre-sputter: 5 min Time: 4 min Power: 50 W Ar: 100 sccm (50%)	Ramp from 30 W to 50 W with 10 W/min (closed shutter)
	Denton: Pt	Time: 11 min 40 sec Power: 50 W Ar: 100 sccm (50%) Pre-sputter: 1 min	Overall thickness ca. 200 nm After every 5 min sputtering let cool for 5 min!!!
6 – Lift off	Acetone		